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2429 / 00001 PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application No.:

10/822,924

Applicant:

Hinman et al.

Filed:

April 13, 2004

Attorney Docket No.:

82489 / 00001

For:

COMPOSITION AND METHOD FOR MAKING

SILICON-CONTAINING PRODUCTS

Group Art Unit:

Unknown

Customer No.:

20873

Commissioner for Patents P.O. Box 1450

Alexandria, VA 22313-1450

Certificate of Mailing

I hereby certify that the papers enclosed herein are being deposited with the United States Postal Service via first class mail with sufficient postage, in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450:

Mark R Backofen

July 13, 2004 Date of Deposit

Sir:

TRANSMITTAL OF INFORMATION DISCLOSURE STATEMENT

Pursuant to the duty of disclosure under 37 C.F.R. §1.56, Applicant submits this statement. This submittal is made in accordance with 37 C.F.R. §§1.97 and 1.98 and §609 of the Manual of Patent Examining Procedure. The patents, publications and other information herein are listed on the attached Form PTO-1449. Copies of the listed references are submitted herewith.

In addition to the references listed on the attached Form PTO-1449, the inventor has indicated that, based upon its title, J. Liu, "Synthesis and Surface Chemistry Modifications of Silica from White Rice Husk Ash and Sulfuric Acid", Chemistry-Peking, 1998, No. 8, pg 42-43, may be relevant to the present invention. However, we have been unable to secure a copy of this

reference or its abstract.

Applicant hereby expressly reserves the right to swear behind the effective dates of any of the above patents and other publications and to question the relevance and materiality of the Patents and Publications listed herein, in whole, in part, or in combination, subsequent to filing this Information Disclosure Statement.

It is believed no fee is due for submission of this paper. If this is incorrect, the Commissioner is hereby authorized to charge any fee due to Locke Liddell & Sapp LLP Deposit Account No. 12-1781.

Mark R. Backofen

Reg. No. 51,423

Date: July 13, 2004

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FORM 98-3

FORM PTO-1449 RTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE (Rev. 2-32)

ATTY. DOCKET NO. 82429 / 00001

SERIAL NO. 10/822,924 Sheet 1 of 3

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

APPLICANT Hinman et al.

(Use several sheets if necessary)

FILING DATE 04/13/04

GROUP Unknown

		U.S. PATENT I	OCUMENTS			
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	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO
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/EMJ/	2144498 C1	01-20-2000	Russia	C01B	33/12	X

EODEICN DATENT DOCUMENTS

EXAMINER

DATE CONSIDERED

/Edward M. Johnson/ (10/26/2008)

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

			Sheet 2 of 3					
FORM PTO-144 (Rev. 2-32)	9 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. 82429 / 00001	SERIAL NO. 10/822,924					
	NFORMATION DISCLOSURE STATEMENT BY APPLICANT	APPLICANT Hinman et al.						
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/EMJ/

			Sheet 3 of 3		
FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE (Rev. 2-32) PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. 82429 / 00001	SERIAL NO. 10/822,924		
	ORMATION DISCLOSURE ATEMENT BY APPLICANT	APPLICANT Hinman et al.			
(Use	several sheets if necessary)	FILING DATE 04/13/04	GROUP Unknown		
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